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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/814,985	03/31/2004	Neal R. Rueger	872-0102US	1278
29855 WONG, CABI	7590 11/15/2007 ELLO, LUTSCH, RUTH	ERFORD & BRUCCULERI,	EXAM	INER 、
L.L.P.			KACKAR, RAM N	
20333 SH 249 SUITE 600			ART UNIT '	PAPER NUMBER
HOUSTON, T	X 77070		1792	
			MAIL DATE	DELIVERY MODE
			11/15/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

		Application No.	Applicant(s)		
Office Action Summary		10/814,985	RUEGER, NEAL R.		
		Examiner	Art Unit		
		Ram N. Kackar	1792		
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with the c	orrespondence address		
A SH WHIC - Exter after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DANS IN THE MAIL	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from 1. cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).		
Status					
1)⊠	Responsive to communication(s) filed on <u>28 September 2007</u> .				
· —	This action is FINAL. 2b) ☐ This action is non-final.				
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.				
	closed in accordance with the practice under E	:x рапе Quayle, 1935 С.D. 11, 43	55 O.G. 213.		
Disposit	ion of Claims				
5)□ 6)⊠	Claim(s) <u>1-23 and 44-70</u> is/are pending in the aday of the above claim(s) <u>2,12 and 44-70</u> is/are Claim(s) is/are allowed.  Claim(s) <u>1,3-11 and 13-23</u> is/are rejected.  Claim(s) is/are objected to.				
	Claim(s) are subject to restriction and/o	r election requirement.			
Applicat	ion Papers				
10)	The specification is objected to by the Examine The drawing(s) filed on is/are: a) acc Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex	epted or b) objected to by the drawing(s) be held in abeyance. Se tion is required if the drawing(s) is ob	e 37 CFR 1.85(a). ojected to. See 37 CFR 1.121(d).		
Priority	under 35 U.S.C. § 119				
12) <u>□</u> a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea. See the attached detailed Office action for a list	s have been received. s have been received in Applicat rity documents have been receiv u (PCT Rule 17.2(a)).	tion No red in this National Stage		
2)  Noti 3)  Info	nt(s)  ce of References Cited (PTO-892)  ce of Draftsperson's Patent Drawing Review (PTO-948)  rmation Disclosure Statement(s) (PTO/SB/08)  er No(s)/Mail Date	4) Interview Summar Paper No(s)/Mail D 5) Notice of Informal 6) Other:	Date		

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#### **DETAILED ACTION**

# Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

2. Claims 1, 3-4 and 8-10 are rejected under 35 U.S.C. 102(b) as being anticipated by Fujimura et al (US 6007671).

Fujimura et al discloses a plasma chamber (Fig 1-1) for detecting a sample gas by exciting it in a plasma cavity (3). Further, Fujimura et al disclose determining a flow of sample gas (for example hydrogen by actinometry- as in Col 11- lines 33-36) when combined with a reference gas (H<sub>2</sub>O as in Fig 1, Fig 7 and Col 10 lines 57-59) when the combination is excited together in the plasma chamber. The reference gas is not disclosed passing through any process chamber. The excitation chamber is disclosed to comprise a cylindrical cavity for receiving the processing gas.

The limitation "wherein the processing gas was used to process a work piece in the processing chamber" is a process limitation and is not given any weight in this apparatus claim.

Regarding the limitation of couplable, since the cylindrical excitation chamber shows gas inlet it is couplable to any source of gas.

Claim 10 is directed to an intended use.

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### Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 1, 3-11 and 13-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Gary Powell (US 6538734) in view of Fujimura et al (US 6007671).

Gary Powell discloses a reaction chamber (101) for deposition or etch processing (Col 1 lines 10-20). Further, Gary Powell discloses an excitation chamber (105) for detecting a sample gas by exciting it to emit radiation representing its chemical composition (Abstract) and teaches that this excitation chamber could be coupled to the reaction chamber to analyse a sample of exhaust gas coming out of plasma processing in the reaction chamber. As a further aspect Gary Powell discloses determining a flow of unknown sample gas when combined with a known flow of reference gas (Abstract and Col 1 lines 34-37) when the combination is excited together in the excitation chamber. The excitation chamber is disclosed to comprise a cylindrical cavity for receiving the processing gas (Fig 2-235) and a reference gas (Col 1 line 33-37, Col 7 lines 31-40 and Col 8 lines 7-14). The sampled gas could be exhaust gas of a process or its representative (Col 2 lines 7-14). Further disclosed is an energy source coupled inductively to the excitation chamber for excitation of the gas (203), flange for processing gas (Fig 2-221), window for monitoring the plasma (237), fiber optics (208), a computer (112) to receive and analyze the spectrum and to control (Abstract). The process could be plasma or non-plasma (Col 7 lines 31-40).

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As discussed above, Gary Powell teaches the presence of both reference gas and sample gas in the excitation chamber for the disclosed method of analysis but does not disclose the mechanism or plumbing needed to accomplish this.

Therefore, to provide two inlets- one dedicated for reference gas and one dedicated for sample gas- coupled to the excitation chamber so as to include reference gas with sample gas in the excitation chamber in order to get the analytical advantage according to the teaching of Gary Powell would have been obvious to one of ordinary skill in the art at the time of invention.

Having a dedicated input for reference gas has the obvious advantage that a self contained unit with a dedicated port could be designed for any number or type of reference gases and could be attached to any process chamber without any modification to it, since on a process chamber, gas inlet ports are generally specific to a certain process.

Fujimura et al discloses a plasma chamber (Fig 1-1) for detecting a sample gas by exciting it in a plasma cavity (3). Further, Fujimura et al disclose determining a flow of sample gas (for example hydrogen by actinometry- as in Col 11- lines 33-36) when combined with a reference gas (H<sub>2</sub>O as in Fig 1, Fig 7 and Col 10 lines 57-59) when the combination is excited together in the plasma chamber. The reference gas is not disclosed passing through any process chamber. The excitation chamber is disclosed to comprise a cylindrical cavity for receiving the processing gas.

Therefore it would have been obvious for one of ordinary skill in the art at the time of invention to provide for inlets for reference gas in addition to exhaust gas to enable determination of exhaust gas according to the teaching of Gary Powell.

The limitation of "wherein the reference gas does not pass through the processing chamber" is an intended use limitation and does not point to any structural limitation. Further, claim 10 is also directed to an intended use.

## Response to Arguments

Applicant's arguments filed 9/28/2007 have been fully considered but they are not persuasive.

Applicant's arguments against the reference of Fujimura et al are not persuasive since the structure disclosed reads on the limitations. The fact that there may be processing down-stream does not have any bearing on the limitations of the claims as recited and those of the reference as disclosed. Applicant argues that the inlet could not be coupleable to a process chamber is not persuasive. Since the claims are for apparatus, the question is, is there is any reason the inlet could not be coupled to a process chamber. The answer is clearly negative. Further, the process chamber in the subsequent claim limitation refers to this hypothetical process chamber and not a process chamber down-stream.

#### Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE

MONTHS from the mailing date of this action. In the event a first reply is filed within TWO

MONTHS of the mailing date of this final action and the advisory action is not mailed until after

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the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ram N. Kackar whose telephone number is 571 272 1436. The examiner can normally be reached on M-F 8:00 A.M to 5:P.M.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on 571 272 1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Ram Kackar

Primary Examiner AU 1763